

**Amendment and Response**

Applicant: Craig K. Carlson-Stevermer

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Title: WAFER STAGING PLATFORM

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**IN THE SPECIFICATION**

Please replace the paragraph beginning at page 4, line 2 with the following rewritten paragraph:

The handling system of the present invention is best shown in Figures 14-16. In accordance with one of the features of the invention, the handling system includes the novel and unique wafer staging platform 30 as shown best in Figures 14-15 that provides both a staging area 32 for a wafer waiting to be processed, and a temporary location 34 to place a processed wafer while the staged wafer is presented to the processing tool. Figure 16 best illustrates the layout of the wafer handling system of the present invention with this wafer staging platform 30.

Please replace the paragraph beginning at page 4, line 10 with the following rewritten paragraph:

Other features of the wafer staging platform 30 include a vacuum system 40 including vacuum lines 42, 44 for holding the wafers securely in place, and wafer sensing to allow wafer detecting by the processing tool. Wafer sensing can be performed by either a vacuum sensor 46 or an optical sensor 48 depending on the application.